GAS SUPPLY METHOD, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, SUBSTRATE PROCESSING APPARATUS, PROGRAM, AND FLOW RATE CONTROLLER

ABSTRACT

A technique is provided which includes: a first process of supplying a gas to a container while controlling a flow rate of the gas by regulating a degree of valve opening of a valve installed at a gas supply line; and a second process of supplying the gas to the container by regulating the degree of valve opening based on an internal pressure of the container.

FIG. 5